

# Schedule of Events

## 59TH DEVICE RESEARCH CONFERENCE

### SUNDAY PM, JUNE 24<sup>TH</sup>, 2001

Registration ..... 4:00PM–9:00PM  
Location ..... McKenna Hall  
Welcoming Reception ..... 6:30PM–8:30PM  
Location ..... McKenna Hall

### MONDAY AM, JUNE 25<sup>TH</sup>, 2001

Registration ..... 7:30AM–5:00PM  
Location ..... McKenna Hall  
Plenary Session ..... 8:30AM  
Location ..... DeBartolo Hall

### MONDAY PM, JUNE 25<sup>TH</sup>, 2001

Session II.A. Silicon Devices ..... 2:00PM  
Session II.B. III-V Devices and Sources ..... 2:00PM  
Session III. Poster Session ..... 5:30PM  
Poster Session Reception ..... 5:30 PM  
Location ..... DeBartolo Hall

### TUESDAY AM, JUNE 26<sup>TH</sup>, 2001

Registration ..... 7:30AM–5:00PM  
Location ..... McKenna Hall  
Session IV. Emerging Technologies ..... 9:00AM

### TUESDAY PM, JUNE 26<sup>TH</sup>, 2001

Session V.A. Novel Devices ..... 2:00PM  
Session V.B. Detectors ..... 2:00PM  
Conference Picnic ..... 6:00PM–8:00PM  
Location ..... St. Mary's Lake  
Rump Session ..... 8:30PM  
Location ..... Debartolo Hall

### WEDNESDAY AM, JUNE 27<sup>TH</sup>, 2001

Registration ..... 7:30AM–1:00PM  
Location ..... McKenna Hall  
Joint Plenary Session with EMC ..... 8:20AM  
Session VI.A. Nanostructure Modeling ..... 10:00AM  
Session VI.B. Displays ..... 10:00AM

### WEDNESDAY PM, JUNE 27<sup>TH</sup>, 2001

Session VII.A. TFTs ..... 2:00PM  
Session VII.B. Wide Bandgap Semiconductors ..... 2:00PM

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- I-1** “SOI and Nanoscale MOSFETs” *Chenming Hu*<sup>1</sup>; <sup>1</sup>University of California, Department of Electrical Engineering and Computer Sciences, Berkeley, CA 94720 USA
- I-2** “Vertical Cavity Surface Emitting Laser - Exploratory, Emerging, or Disruptive?” *K. Iga*<sup>1</sup>; <sup>1</sup>Tokyo Institute of Technology, 4259 Nagatsuta, Midoriku, Yokohama 226-8502 Japan
- I-3** “Low-Noise, High-Speed Avalanche Photodiodes” *Joe C. Campbell*<sup>1</sup>; <sup>1</sup>The University of Texas at Austin, Microelectronics Research Center, 10100 Burnet Road, Mail Code R9950, Austin, TX 78712 USA
- I-4** “Status, Prospects and Commercialization of SiC Power Devices” *Dietrich Stephani*<sup>1</sup>; <sup>1</sup>SiCED Electronics Development GmbH & Co. KG, Paul-Gossen-Str. 100, D91052 Erlangen, Germany

## SESSION II.A. SILICON DEVICES

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- II.A.-1** “High-K Gate Dielectrics for Sub-100 nm CMOS Technology” *Dim-Lee Kwong*<sup>1</sup>; <sup>1</sup>The University of Texas at Austin, Microelectronics Research Center, 10100 Burnet Road, Bldg. 160, Austin, TX 78758 USA
- II.A.-2** “Fast Write Time and Long Retention 1T Memory” *Albert Chin*<sup>1</sup>; M. Y. Yang<sup>1</sup>; S. B. Chen<sup>1</sup>; C. L. Sun<sup>2</sup>; S. Y. Chen<sup>2</sup>; <sup>1</sup>National Chiao Tung University, Dept. of Electronics Engineering, Hsinchu, Taiwan; <sup>2</sup>National Chiao Tung University, Dept. of Materials Science Engineering, Hsinchu, Taiwan
- II.A.-3** “Physical Origin of SILC and Noisy Breakdown in Very Thin Silicon Nitride Gate Dielectric” *Igor Polishchuk*<sup>1</sup>; Tsu-Jae King<sup>1</sup>; Chenming Hu<sup>1</sup>; <sup>1</sup>University of California at Berkeley, Department of Electrical Engineering and Computer Sciences, Berkeley, CA 94720 USA
- II.A.-4** “Low-Power CMOS at  $V_{dd}=4kT/q$ ” *Andres Bryant*<sup>1</sup>; Jeffrey Brown<sup>1</sup>; Peter Cottrell<sup>1</sup>; Mark Ketchen<sup>2</sup>; John Ellis-Monaghan<sup>1</sup>; E. J. Nowak<sup>1</sup>; <sup>1</sup>IBM Microelectronics Division, Essex Junction, VT 05452 USA; <sup>2</sup>IBM T. J. Watson Research Center, Yorktown Heights, NY 10598 USA
- II.A.-5** “A Sub-40nm Body Thickness N-Type FinFET” *David M. Fried*<sup>1</sup>; Arthur P. Johnson<sup>1</sup>; Edward J. Nowak<sup>1</sup>; Jed H. Rankin<sup>1</sup>; Christa R. Willets<sup>1</sup>; <sup>1</sup>IBM Microelectronics Division, Essex Junction, VT 05452 USA
- II.A.-6** “Quasi-Planar NMOS FinFETs with Sub-100nm Gate Lengths” *Nick Lindert*<sup>1</sup>; Yang-Kyu Choi<sup>1</sup>; Leland Chang<sup>1</sup>; Erik Anderson<sup>2</sup>; Wenchin Lee<sup>3</sup>; Tsu-Jae King<sup>1</sup>; Jeffrey Bokor<sup>1</sup>; Chenming Hu<sup>1</sup>; <sup>1</sup>University of California at Berkeley, Department of Electrical Engineering and Computer Sciences, Berkeley, CA 94709 USA; <sup>2</sup>X-Ray Optics, Lawrence Berkeley National Laboratory, Berkeley, CA USA; <sup>3</sup>Intel Corporation, Logic Technology Development, Hillsboro, OR USA
- II.A.-7** “High Performance of Planar Double Gate MOSFETs with Thin Backgate Dielectrics” *Erin C. Jones*<sup>1</sup>; Meikei Jeong<sup>2</sup>; Thomas Kanarsky<sup>2</sup>; Omer Dokumaci<sup>2</sup>; Ronnen A. Roy<sup>1</sup>; Leathen Shi<sup>1</sup>; Toshiharu Furukawa<sup>3</sup>; Robert J. Miller<sup>1</sup>; H-S Philip Wong<sup>1</sup>; <sup>1</sup>IBM T. J. Watson Research Center, Yorktown Heights, NY 10598 USA; <sup>2</sup>IBM SRDC, Hopewell Junction, NY 12533 USA; <sup>3</sup>IBM Microelectronics Division, Essex Junction, VT 05254 USA
- II.A.-8** “Si<sub>1-x</sub>Ge<sub>x</sub> Channel Vertical PMOSFET with Asymmetric Ge Profile” *Xiangdong Chen*<sup>1</sup>; Qiqing Ouyang<sup>1</sup>; Sankaran Kartik Jayanarayanan<sup>1</sup>; Freek E. Prins<sup>1</sup>; Sanjay Banerjee<sup>1</sup>; <sup>1</sup>The University of Texas at Austin, Microelectronics Research Center, 10100 Burnet Road, Bldg. 160, Austin, TX 78758 USA

## SESSION II.B. III-V DEVICES AND SOURCES

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- II.B.-1** “Optical Interconnections to Silicon Integrated Circuits” *David Miller*<sup>1</sup>; <sup>1</sup>Stanford University, Stanford, CA 94305 USA
- II.B.-2** “Temperature-Dependent Large Signal Modulation and Auger Recombination in In<sub>0.4</sub>Ga<sub>0.6</sub>As Quantum-Dot Lasers” *S. Ghosh*<sup>1</sup>; P. Bhattacharya<sup>1</sup>; E. Stoner<sup>1</sup>; H. Jiang<sup>2</sup>; S. Nuttinck<sup>3</sup>; J. Singh<sup>1</sup>; J. Laskar<sup>3</sup>; <sup>1</sup>University of Michigan, Solid State Electronics Laboratory, Department of Electrical Engineering and Computer Science, Ann Arbor, MI 48109 USA; <sup>2</sup>Broadcom

- II.B-3** “ZnSe-Based Laser Diodes for the 560 nm Spectral Region” *M. Klude*<sup>1</sup>; G. Alexe<sup>1</sup>; C. Kruse<sup>1</sup>; T. Passow<sup>1</sup>; D. Hommel<sup>1</sup>; <sup>1</sup>Institut für Festkörperphysik, Universität Bremen, 28359 Bremen, Germany
- II.B-4** “*NpN* InGaAsN-Based Heterojunction Bipolar Transistors with  $f_{max}=60\text{GHz}$ ” *C. Monier*<sup>1</sup>; A. G. Baca<sup>1</sup>; F. Newman<sup>2</sup>; P. C. Chang<sup>1</sup>; N. Y. Li<sup>2</sup>; H. Q. Hou<sup>2</sup>; E. Armour<sup>3</sup>; R. Stall<sup>3</sup>; <sup>1</sup>Sandia National Laboratories, Albuquerque, NM 87185 USA; <sup>2</sup>Emcore Corporation, Emcore Photovoltaics, Albuquerque, NM 87123 USA; <sup>3</sup>Emcore Corporation, Sommerset, NJ 08873 USA
- II.B-5** “Noise Characteristics of Highly Strained InGaP/InGaAs p-HEMTs Grown on Patterned Substrates by Using Compound-Source MBE” *Jeong Hoon Kim*<sup>1</sup>; Sung-June Jo<sup>1</sup>; Jong-In Song<sup>1</sup>; <sup>1</sup>K-JIST, Department of Information and Communications, 1 Oryong-dong Buk-gu, Kwangju, 500-712 Korea
- II.B-6** “A Flip-Flop Based on Monolithic Integration of InAs/AlSb/GaSb RITDs and InAlAs/InGaAs/InP HEMTs” *P. Fay*<sup>1</sup>; Y. Xu<sup>1</sup>; G. H. Bernstein<sup>1</sup>; A. Gonzalez<sup>2</sup>; P. Mazumder<sup>2</sup>; D. H. Chow<sup>3</sup>; J. N. Schulman<sup>3</sup>; <sup>1</sup>University of Notre Dame, Department of Electrical Engineering, Notre Dame, IN 46556 USA; <sup>2</sup>University of Michigan, Department of Electrical Engineering and Computer Science, Ann Arbor, MI 48109 USA; <sup>3</sup>HRL Laboratories, Malibu, CA 90265 USA
- II.B-7** “Monolithic Integration of InAlAs/InGaAs Enhancement and Depletion (E/D)-Mode Metamorphic HEMTs on GaAs Substrate” *D. C. Dumka*<sup>1</sup>; W. E. Hoke<sup>2</sup>; P. J. Lemonias<sup>2</sup>; R. Schwindt<sup>1</sup>; G. Cueva<sup>1</sup>; I. Adesida<sup>1</sup>; <sup>1</sup>University of Illinois at Urbana-Champaign, Microelectronics Laboratory, Department of Electrical and Computer Engineering, 208 Wright Street, Urbana, IL 61801 USA; <sup>2</sup>Raytheon RF Components, 362 Lowell Street, Andover, MA 01810 USA

### SESSION III. POSTER SESSION

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- III-1** “Dual-Channel SOI LIGBT with Improved Latch-Up and Forward Voltage Drop Characteristics” *Woo-Beom Choi*<sup>1</sup>; Woong-Je Sung<sup>1</sup>; Yong-Il Lee<sup>1</sup>; Man Young Sung<sup>1</sup>; <sup>1</sup>Korea University, Department of Electrical Engineering, 1, 5-ka, Anam-dong, Sungbuk-ku, Seoul 136-701, Korea
- III-2** “Chaos Generator MMIC’s Using Resonant Tunneling Diodes” *K. Maezawa*<sup>1</sup>; Y. Kawano<sup>1</sup>; Y. Ohno<sup>1</sup>; S. Kishimoto<sup>1</sup>; T. Mizutani<sup>1</sup>; <sup>1</sup>Nagoya University, Graduate School of Engineering, Furo-cho, Chikusa-ku, Nagoya-shi, 464-8603, Japan
- III-3** “High Detectivity Solar Blind AlGaIn Metal-Semiconductor-Metal Detector” *Jean-Luc Reverchon*<sup>1</sup>; Jean-Yves Duboz<sup>1</sup>; Fabrice Semond<sup>2</sup>; Nicolas Grandjean<sup>2</sup>; Jean Massies<sup>2</sup>; <sup>1</sup>Laboratoire Central de Recherches, THALES, 91404 ORSAY, Cedex, France; <sup>2</sup>CRHEA-CNRS, rue Bernard Gregory, Sophia Antipolis, 06560 Valbonne, France
- III-4** “Characterization of a 0.1  $\mu\text{m}$  MOSFET Using Cross-Sectional Scanning Tunneling Microscopy” *T. Okui*<sup>1</sup>; S. Hasegawa<sup>1</sup>; H. Nakashima<sup>1</sup>; H. Fukutome<sup>2</sup>; H. Arimoto<sup>2</sup>; <sup>1</sup>Osaka University, The Institute of Scientific and Industrial Research, 8-1 Mihogaoka, Ibaraki, Osaka 567-0047 Japan; <sup>2</sup>Fujitsu Laboratories Ltd., 10-1 morinosato-wakamiya, Atsugi, Kanagawa 243-0197 Japan
- III-5** “Nanoscale MOSFETs Scaling” *Yehuda Naveh*<sup>1</sup>; Victor Sverdlov<sup>1</sup>; Konstantin Likharev<sup>1</sup>; <sup>1</sup>State University of New York, Stony Brook, NY 11794-3800 USA
- III-6** “50 nm Vertical Surround Gate MOSFET with S-Factor of 75mV/dec” *Ruigang Li*<sup>1</sup>; Yaohui Zhang<sup>2</sup>; Yang Lu<sup>2</sup>; Daniel Sung Choi<sup>2</sup>; Marie Luo<sup>3</sup>; Kang L. Wang<sup>2</sup>; <sup>1</sup>University of California at Los Angeles, Electrical Engineering Department, Room 56-125B ENGR IV, Los Angeles, CA 90095-1594 USA; <sup>2</sup>University of California at Los Angeles, Electrical Engineering Department, Los Angeles, CA 90095-1594 USA; <sup>3</sup>Conexant Systems Inc., 4311 Jamboree, Newport Beach, CA 92660 USA
- III-7** “Hyperspectral Imaging of Breakdown in InAlAs/InGaAs HEMTs: A Comparative Study” *Mark Somerville*<sup>1</sup>; Jon Rameau<sup>1</sup>; Nii Moi Addo<sup>1</sup>; <sup>1</sup>Vassar College, Department of Physics and Astronomy, 124 Raymond Avenue, Poughkeepsie, NY 12604 USA
- III-8** “Extension of Safe-Operating-Area by Optimizing Body-Current in Submicron LDMOS Transistors” *S. K. Lee*<sup>1</sup>; Y. C. Choi<sup>1</sup>; J. H. Kim<sup>1</sup>; C. J. Kim<sup>1</sup>; H. S. Kang<sup>1</sup>; C. S. Song<sup>1</sup>; <sup>1</sup>Fairchild Korea Semiconductor Co. New Technology Development Team, 82-3 Dodang-Dong, Wonmi-Ku, Puchon, Kyonggi-Do, Korea
- III-9** “Computer Analysis of Geometry and Strain Effects in Silicon Nano-Crystal Floating-Gate Flash Memory Devices” *Aaron Thean*<sup>1</sup>; Jean-Pierre Leburton<sup>1</sup>; <sup>1</sup>University of Illinois, Beckman Institute for Advanced Science & Technology, Dept. of Electrical & Computer Engineering, Urbana, IL 61801 USA

- III-10** “An Extension of McKelvey’s One-Flux Method to Energy Space” *W. R. McKinnon*<sup>1</sup>; <sup>1</sup>National Research Council, Ottawa, K1A 0R6, Canada
- III-11** “Characterization of Midgap Tungsten Gate MOSFETs” *Huilin Shang*<sup>1</sup>; Marvin H. White<sup>1</sup>; Kathryn W. Gaurini<sup>2</sup>; Edward Cartier<sup>2</sup>; Paul Solomon<sup>2</sup>; <sup>1</sup>Lehigh University, EECS Department, Sherman Fairchild Lab, Bethlehem, PA 18015 USA; <sup>2</sup>IBM T. J. Watson Research Center, P. O. Box 218, Yorktown Heights, NY 10598 USA
- III-12** “ESD Protection for High Voltage LDMOS with Sense FET” *Y. S. Choi*<sup>1</sup>; J. J. Kim<sup>1</sup>; C. K. Jeon<sup>1</sup>; M. H. Kim<sup>1</sup>; S. L. Kim<sup>1</sup>; H. S. Kang<sup>1</sup>; C. S. Song<sup>1</sup>; <sup>1</sup>Fairchild Semiconductor, Process R&D Group, 82-3 Dodang-Dong, Wonmi-Ku, Puchon, Kyonggi-Do, 420-711, Korea
- III-13** “Mixed Mode Double-Gate FET Model” *P. M. Solomon*<sup>1</sup>; <sup>1</sup>IBM T. J. Watson Research Center, Yorktown Heights, NY 10598 USA
- III-14** “Low Programming Voltages and Long Retention Time in Metal Nanocrystal EEPROM Devices” *Zengtao Liu*<sup>1</sup>; Venkat Narayanan<sup>1</sup>; Myongseob Kim<sup>1</sup>; Gen Pei<sup>1</sup>; Edwin C. Kan<sup>1</sup>; <sup>1</sup>Cornell University, Electrical and Computer Engineering, Ithaca, NY 14853 USA.
- III-15** “High Performance AlGaIn/GaN HEMTs with Recessed Gate on Sapphire Substrate” *Y. Sano*<sup>1</sup>; T. Yamada<sup>1,2</sup>; J. Mita<sup>1,2</sup>; K. Kaifu<sup>1</sup>; H. Ishikawa<sup>3</sup>; T. Egawa<sup>3</sup>; M. Umeno<sup>3</sup>; <sup>1</sup>Oki Electric Industry Co., Ltd., Corporate Research Laboratory, 550-5 Higashiawakawa, Hachioji, Tokyo 193-8550, Japan; <sup>2</sup>Ultra-Low-Loss Power Device Technology Research Body; <sup>3</sup>Nagoya Institute of Technology, Gokiso-cho, Showa-ku, Nagoya 466-8555, Japan
- III-16** “A Comparison of Bulk and SOI Deep Sub-Micron MOSFET Small-Signal Behavior in the High-Frequency Regime Beyond 10GHz” *D. Goldman*<sup>1</sup>; T. Gafron<sup>1</sup>; C.-S. Kim<sup>1</sup>; Q. Nguyen<sup>1</sup>; F. Burke<sup>1</sup>; B. Cheek<sup>1</sup>; S. Parke<sup>1</sup>; <sup>1</sup>Boise State University, Dept. of Electrical and Computer Engineering, Boise, ID 83725 USA
- III-17** “Threshold Voltage Shift by Quantum Confinement in Ultra-Thin Body Device” *Yang-Kyu Choi*<sup>1</sup>; Daewon Ha<sup>1</sup>; Tsu-Jae King<sup>1</sup>; Chenming Hu<sup>1</sup>; <sup>1</sup>University of California at Berkeley, Department of Electrical Engineering and Computer Sciences, Berkeley, CA 94720 USA
- III-18** “A New and Accurate Quantum Mechanical Compact Model for NMOS Gate Capacitance” *S. Mudanai*<sup>1</sup>; L. F. Register<sup>1</sup>; A. F. Tasch<sup>1</sup>; S. K. Banerjee<sup>1</sup>; <sup>1</sup>The University of Texas at Austin, Microelectronics Research Center, Mail Code R9950, Austin, TX 78712 USA
- III-19** “An Intrinsically Coupled HBT/RTD Device Enabling an Adjustable Peak-Current-Density” *P. Velling*<sup>1</sup>; M. Agethen<sup>1</sup>; W. Prost<sup>1</sup>; G. Janssen<sup>2</sup>; R. M. Bertenburg<sup>2</sup>; F. J. Tegude<sup>1</sup>; <sup>1</sup>Gerhard-Mercator University, Solid State Electronics Department, 47057 Duisburg, Germany; <sup>2</sup>IPAG - Innovative Processing AG, Lotharstrasse 55 (ZHO), 47057 Duisburg, Germany
- III-20** “Excellent DC Characteristics of HEMTs on Semi-Insulating Silicon Carbide Substrate” *S. Arulkumaran*<sup>1</sup>; T. Egawa<sup>1</sup>; G. Zhao<sup>1</sup>; H. Ishikawa<sup>1</sup>; M. Umeno<sup>1</sup>; <sup>1</sup>Nagoya Institute of Technology, Research Center for Micro-Struction Devices, Gokiso-cho, showa-ku, Nagoya 466-8555, Japan
- III-21** “A Quantum Dot FET - A Future Playground of Quantum State Manipulation” *Kanji Yoh*<sup>1</sup>; Hironobu Kazama<sup>1</sup>; Yoshito Katano<sup>1</sup>; <sup>1</sup>Hokkaido University, Research Center for Interface Quantum Electronics, N 13, W8, Kita-ku, Sapporo, Hokkaido 060-8628 Japan
- III-22** “Sub-40nm V-Groove MOSFETs” *J. Appenzeller*<sup>1</sup>; R. Martel<sup>1</sup>; Ph. Avouris<sup>1</sup>; J. Knoch<sup>2</sup>; Y. Lu<sup>3</sup>; K. L. Wang<sup>3</sup>; J. Scholvin<sup>4</sup>; J. A. del Alamo<sup>4</sup>; P. Rice<sup>5</sup>; P. Solomon<sup>1</sup>; <sup>1</sup>IBM T. J. Watson Research Center, Yorktown Heights, NY 10598 USA; <sup>2</sup>II. Physikalisches Institut, RWTH Aachen, Templergraben 55, 52056 Aachen, Germany; <sup>3</sup>University of California at Los Angeles, Los Angeles, CA 90095 USA; <sup>4</sup>Massachusetts Institute of Technology, 77 Massachusetts Avenue, Cambridge, MA 02139 USA; <sup>5</sup>IBM Almaden Research Center, San Jose, CA 95120 USA
- III-23** “Terahertz Plasma-Wave Excitation in 80-nm Gate-Length GaAs MESFET by Photomixing Long-Wavelength CW Laser Sources” *Taiichi Otsuji*<sup>1</sup>; Yoshihiro Kanamaru<sup>1</sup>; Hajime Kitamura<sup>1</sup>; Shin Nakae<sup>1</sup>; <sup>1</sup>Kyushu Institute of Technology, Department of Control Science and Engineering, Iizuka, Fukuoka, 820-8502, Japan
- III-24** “Fabrication of InP DHBTs with 0.1µm Wide Emitter” *T. Arai*<sup>1</sup>; H. Nagatsuka<sup>1</sup>; Y. Miyamoto<sup>1</sup>; K. Furuya<sup>1</sup>; <sup>1</sup>Tokyo Institute of Technology, Department of Physical Electronics, 2-12-1 O-okayama, Meguro-ku, Tokyo 152-8552, Japan

**III-25** “Characteristics of Submicron HBTs in the 140-220 GHz Band” *M. Urteaga*<sup>1</sup>; D. Scott<sup>1</sup>; T. Matthew<sup>1</sup>; S. Krishnan<sup>1</sup>; Y. Wei<sup>1</sup>; M. Dahlstrom<sup>1</sup>; M. Rodwell<sup>1</sup>; <sup>1</sup>University of California at Santa Barbara, Department of ECE, Santa Barbara, CA 93106 USA

**III-26** “A Quantum-Dot Cellular Automata Shift Register” *Ravi Kummmamaru*<sup>1</sup>; Aexei O. Orlov<sup>1</sup>; John P. Timler<sup>1</sup>; R. Ramasubramaniam<sup>1</sup>; Craig S. Lent<sup>1</sup>; Gary H. Bernstein<sup>1</sup>; Gregory L. Snider<sup>1</sup>; <sup>1</sup>University of Notre Dame, Department of Electrical Engineering, Notre Dame, IN 46556 USA

## SESSION IV. EMERGING TECHNOLOGIES

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**IV-1** “Nanotube Nanoelectronics” *Paul L. McEuen*<sup>1,2</sup>; J. Park<sup>2,3</sup>; A. Bachtold<sup>2,3</sup>; M. Woodside<sup>2,3</sup>; M. S. Fuhrer<sup>2,3</sup>; M. Bockrath<sup>2,3</sup>; L. Shi<sup>4</sup>; A. Majumdar<sup>4</sup>; P. Kim<sup>2,3</sup>; <sup>1</sup>Cornell University, Laboratory of Atomic and Solid State Physics, Ithaca, NY 14853 USA; <sup>2</sup>University of California, Department of Physics, Berkeley, CA 94720 USA; <sup>3</sup>University of California, Materials Sciences Division, Lawrence Berkeley National Laboratory, Berkeley, CA 94720 USA; <sup>4</sup>University of California, Department of Mechanical Engineering, Berkeley, CA 94720 USA

**IV-2** “Molecule/Metal and Molecule/Semiconductor Heterostructures for Electronic Devices” *David B. Janes*<sup>1</sup>; Purdue University, School of Electrical and Computer Engineering, W. Lafayette, IN 47907 USA

**IV-3** “Integrated RF Passive Components - Discrete vs. Distributed” *J. N. Burghartz*<sup>1</sup>; K. T. Ng<sup>1</sup>; N. P. Pham<sup>1</sup>; B. Rejzai<sup>1</sup>; P. Sarro<sup>1</sup>; <sup>1</sup>Delft University of Technology, EC TM-DIMES, Feldmannweg 17, 2600 GB Delft, The Netherlands

**IV-4** “Photonic Crystal Cavities and Waveguides” *A. Scherer*<sup>1</sup>; O. Painter<sup>1</sup>; J. Vuckovic<sup>1</sup>; M. Loncar<sup>1</sup>; D. Dapkus<sup>2</sup>; I. Kim<sup>2</sup>; T. Pearsall<sup>3</sup>; <sup>1</sup>Caltech, MC 200-36, Pasadena, CA 91125 USA; <sup>2</sup>University of Southern California; <sup>3</sup>CERF Corning, Avon France

**IV-5** “Electronic Detection of DNA: Robust Platform for Integrated Devices” *Robert H. Terbrueggen*<sup>1</sup>; Yin-Peng Chen<sup>1</sup>; Hau Duong<sup>1</sup>; Dan Farkas<sup>1</sup>; K. M. Millan<sup>1</sup>; Gary T. Olsen<sup>1</sup>; Nathan Swami<sup>1</sup>; Hai Wang<sup>1</sup>; Handy Yowanto<sup>1</sup>; C. J. Yu<sup>1</sup>; Gary F. Blackburn<sup>1</sup>; Jon Faiz Kayyem<sup>1</sup>; <sup>1</sup>Motorola Clinical Micro Sensors, 757 South Raymond Avenue, Pasadena, CA 91105 USA

## SESSION V.A. NOVEL DEVICES

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**V.A.-1** “Tunable Two-Electron Spin States in Quantum Dot Structures and the Applicability for Making Spin Qubits” *S. Tarucha*<sup>1</sup>; K. Ono<sup>2</sup>; D. G. Austing<sup>3</sup>; S. Sasaki<sup>3</sup>; T. Fujisawa<sup>3</sup>; Y. Tokura<sup>3</sup>; L. P. Kouwenhoven<sup>4</sup>; <sup>1</sup>ERATO Mesoscopic Correlation Project <sup>2</sup>Department of Physics, University of Tokyo, 7-3-1 Bunkyo-ku, Hongo, 7-3-1 Tokyo 113-0033, Japan; <sup>3</sup>NTT Basic Research Laboratories, Morinosato Wakamiya, Atugi-shi, Kanagawa 243-0198, Japan; <sup>4</sup>ERATO Mesoscopic Correlation Project, & Department of Applied Physics, Delft University of Technology, P.O. Box 5046, 2600 GA Delft, The Netherlands.

**V.A.-2** “A Multiple-Valued SRAM with Combined Single-Electron and MOS Transistors” *Hiroshi Inokawa*<sup>1</sup>; Akira Fujiwara<sup>1</sup>; Yasuo Takahashi<sup>1</sup>; <sup>1</sup>NTT Basic Research Laboratories, 3-1 Morinosato Wakamiya, Atsugi-shi, Kanagawa Pref., 243-0198 Japan

**V.A.-3** “Binary-Decision-Diagram Quantum Circuits Based on Schottky Wrap Gate Control of GaAs Honeycomb Nanowires” *Seiya Kasai*<sup>1</sup>; Hideki Hasegawa<sup>1</sup>; <sup>1</sup>Hokkaido University, Research Center for Interface Quantum Electronics and Graduate School of Electronics and Information Engineering, N-13, W-8, Kita-ku, Sapporo 060-8628, Japan

**V.A.-4** “Single Electron Transistors with Sidewall Depletion Gates on a Silicon-On-Insulator Quantum Wire” *D. H. Kim*<sup>1</sup>; K. R. Kim<sup>1</sup>; S.-K. Sung<sup>1</sup>; B. H. Choi<sup>2,3</sup>; S. W. Hwang<sup>2,3</sup>; D. Ahn<sup>2</sup>; J. D. Lee<sup>1</sup>; B.-G. Park<sup>1</sup>; <sup>1</sup>Seoul National University, Inter-University Semiconductor Research Center (ISRC) and School of Electrical Engineering, San 56-1, Shinlim-dong, Kwanak-gu, Seoul 151-742, Korea; <sup>2</sup>University of Seoul, Institute of Quantum Information Processing and Systems (iQUIPS), Seoul 130-743, Korea; <sup>3</sup>Korea University, School of Electrical Engineering, Anamdong, Sungbukku, Seoul 136-701, Korea

**V.A.-5** “A Semiconductor GMR Device” *Kanji Yoh*<sup>1</sup>; T. Doi<sup>1</sup>; Y. Katano<sup>1</sup>; S. Abe<sup>2</sup>; H. Ohno<sup>2</sup>; K. Sueoka<sup>2</sup>; K. Mukasa<sup>2</sup>; <sup>1</sup>Hokkaido University, Research Center for Interface Quantum Electronics, N 13, W8, Kita-ku, Sapporo, Hokkaido 060-8628 Japan; <sup>2</sup>Hokkaido University, Graduate School of Electronics and Information Technology, N 13, W8, Kita-ku, Sapporo, Hokkaido 060-8628 Japan

**V.A.-6** “Digital Thin Film Non-Volatile Optical Memory” *Robert C. J. Chil*<sup>1</sup>; A. J. Steckl<sup>1</sup>; <sup>1</sup>University of Cincinnati, Nanoelectronics Laboratory, Cincinnati, OH 45221-0030 USA

**V.A.-7 “Modeling and Design Study of Nanocrystal Memory Devices”** *Min-She<sup>1</sup>*; Ya-Chin King<sup>2</sup>; Tsu-Jae King<sup>1</sup>; Chenming Hu<sup>1</sup>;  
<sup>1</sup>University of California at Berkeley, Department of Electrical Engineering and Computer Sciences, Berkeley, CA 94720 USA;  
<sup>2</sup>National Tsing-Hua University, Department of Electrical Engineering, Hsinchu, Taiwan, R.O.C.

**V.A.-8 “Quasi-Magnetic Fields Revisited: Second-Order Transport Effects in Graded Semiconductors”** *William R. Frensley<sup>1</sup>*;  
<sup>1</sup>University of Texas at Dallas, Richardson, TX 75083 USA

## SESSION V.B. DETECTORS

143–160

**V.B.-1 “Single Electron Transistors as Far-Infrared Photon Detectors”** *O. Astafiev<sup>1</sup>*; V. Antonov<sup>1</sup>; T. Kutsuwa<sup>1</sup>; S. Komiyama<sup>2</sup>;  
<sup>1</sup>Department of Basic Science, University of Tokyo, Komaba 3-8-1, Meguro-ku, Tokyo 153-8902, Japan; <sup>2</sup>Japan Science and  
Technology Corporation (JST) Kawaguchi-shi, Saitama 332-0012, Japan

**V.B.-2 “High-Speed Waveguide Avalanche Photodetectors”** *Geoffrey Kinsey<sup>1</sup>*; R. Sidhu<sup>1</sup>; A. L. Holmes, Jr.<sup>1</sup>; J. C. Campbell<sup>1</sup>; <sup>1</sup>The  
University of Texas at Austin, Microelectronics Research Center, MER 1.608B/R9900, Austin, TX 78712 USA

**V.B.-3 “200-Gbit/s Monolithic Photodiode-Electroabsorption Modulator (PD-EAM) Optical Gate”** *S. Kodama<sup>1</sup>*; T. Ito<sup>1</sup>; N. Watanabe<sup>1</sup>;  
S. Kondo<sup>1</sup>; H. Takeuchi<sup>1</sup>; H. Ito<sup>1</sup>; T. Ishibashi<sup>1</sup>; <sup>1</sup>NTT Photonics Laboratories, Morinsato-Wakamiya 3-1, Atsugi-shi, Kanagawa  
243-0198, Japan

**V.B.-4 “A CMOS-Compatible High-Speed Silicon Lateral Trench Photodetector”** *Min Yang<sup>2</sup>*; Ken Rim<sup>1</sup>; Dennis Rogers<sup>1</sup>; Jeremy  
Schaub<sup>1</sup>; Jeffrey Welsler<sup>1</sup>; Daniel Kuchta<sup>1</sup>; Diane Boyd<sup>2</sup>; <sup>1</sup>IBM T. J. Watson Research Center, P. O. Box 218, Yorktown Heights,  
NY 10598 USA; <sup>2</sup>IBM Microelectronics, Hopewell Junction, NY 12533 USA

**V.B.-5 “High-Temperature Operation of Mid-Infrared ( $\lambda=4\text{-}5\mu\text{m}$ ) Vertical and Lateral InAs/GaAs/AlGaAs Quantum Dot Infrared  
Photodetectors”** *A. D. Stiff<sup>1</sup>*; S. Krishna<sup>1</sup>; P. Bhattacharya<sup>1</sup>; S. Kennerly<sup>1</sup>; <sup>1</sup>University of Michigan, Solid State Electronics  
Laboratory, Department of Electrical Engineering and Computer Science, Ann Arbor, MI 48109-2122 USA; <sup>2</sup>Army Research  
Laboratory, Sensors and Electron Devices Directorate, Adelphi, MD 20783 USA

**V.B.-6 “Normal-incident  $\text{In}_{0.2}\text{Ga}_{0.8}\text{As}/\text{GaAs}$  Quantum Well Infrared Photodetector Employing a p-i-n-i-p Camel Diode Structure”**  
*Heesoo Son<sup>1</sup>*; Jinsung Park<sup>1</sup>; Songcheol Hong<sup>1</sup>; Sung-June Jo<sup>2</sup>; Jong-In Song<sup>2</sup>; <sup>1</sup>KAIST, Department of Electrical Engineering  
and Computer Science, Taejeon 305-701, Korea; <sup>2</sup>K-JIST, Department of Information and Communications, Kwangju 500-712, Korea

**V.B.-7 “High Efficiency, Large Area, InGaAs/InPAs Thermophotovoltaic Cells”** *R. R. Siegiej<sup>1</sup>*; B. Wernsman<sup>1</sup>; S. A. Derry<sup>1</sup>; R. J.  
Wehrer<sup>1</sup>; S. D. Link<sup>1</sup>; M. N. Palmisiano<sup>1</sup>; D. R. Riley<sup>1</sup>; C. S. Murray<sup>2</sup>; F. Newman<sup>2</sup>; J. Hills<sup>2</sup>; <sup>1</sup>Bechtel Bettis, Inc., 814 Pittsburgh-  
McKeesport Blvd, West Mifflin, Pennsylvania 15122; <sup>2</sup>Emcore Photovoltaics, Albuquerque, NM 87123 USA

## SESSION VI.A. NANOSTRUCTURE MODELING

161–172

**VI.A.-1 “Spin-Orbit Interaction of  $2^\circ$  in InAlAs/InAs Hetero-structures”** *Kanji Yoh<sup>1</sup>*; Toshihiro Doi<sup>1</sup>; Shin-ichiro Abe<sup>2</sup>; Yoshito  
Katano<sup>1</sup>; Hiroshi Ohno<sup>2</sup>; Kazuhisa Sueoka<sup>2</sup>; Koichi Mukasa<sup>2</sup>; <sup>1</sup>Hokkaido University, RCIQE, N13, W8, Kita-ku, Sapporo,  
Hokkaido 060-8628 Japan; <sup>2</sup>Hokkaido University, Grad. Sch. of Eng., N13, W8, Kita-ku, Sapporo, Hokkaido 060-8628 Japan

**VI.A.-2 “Thermal Conductivity in Semiconductor Thin Films and Nanowires”** *Jie Zou<sup>1</sup>*; Alexander A. Balandin<sup>1</sup>; <sup>1</sup>University of  
California at Riverside, Dept. of Electl. Eng., Riverside, CA 92521 USA

**VI.A.-3 “Quantum Mechanical Calculation of QCA Molecule Properties”** *Christopher J. Russo<sup>1</sup>*; *Craig S. Lent<sup>1</sup>*; <sup>1</sup>University of  
Notre Dame, Electl. Eng., 275 Fitzpatrick, Notre Dame, IN 46556 USA

**VI.A.-4 “Nano-Transistor Modeling: Two Dimensional Green’s Function Method”** *A. Svizhenko<sup>1</sup>*; M. P. Anantram<sup>1</sup>; T. R. Govindan<sup>1</sup>;  
B. Biegel<sup>1</sup> <sup>1</sup>NASA, Ames Rsrch. Ctr., MS T27A-1, Moffett Field, CA 94035-1000 USA

**VI.A.-5 “A Coupled Schrödinger/Monte Carlo Technique for Quantum-Corrected Device Simulation”** *Brian Winstead<sup>1</sup>*; Umberto  
Ravaoli<sup>1</sup> <sup>1</sup>University of Illinois at Urbana–Champaign, Beckman Inst., Urbana, IL 61801 USA

**VI.A.-6 “Quantitative Prediction of Threshold Voltage Fluctuations in Sub-100 nm MOSFETs by a New Dopant Model”**  
*Hiroyuki Yamamoto<sup>1</sup>*; Yos-himitsu Okada<sup>1</sup>; Nobuyuki Sano<sup>1</sup>; <sup>1</sup>University of Tsukuba, Inst. of Appl. Phys., 1-1-1  
Tennoudai, Tsukuba, Ibaraki, 305-8573 Japan

- VI.B.-1 “High Gamma Coatings for Plasma Display Panels: A Comparison”** *P. K. Bachmann<sup>1</sup>; V. Van Elsbergen<sup>1</sup>; C. McGrath<sup>1</sup>;*  
<sup>1</sup>Phillips Research Laboratories, Weissshausstrasse 2, D-52066 Aachen, Germany
- VI.B.-2 “Rare-Earth Doped GaN Electroluminescent Devices for Robust Flat Panel Displays”** *J. Heikenfeld<sup>1</sup>; A.J. Steckl<sup>1</sup>;*  
<sup>1</sup>University of Cincinnati, Nanoelectronics Lab, Cincinnati, OH 45221-0030 USA
- VI.B.-3 “Novel Three-Color Polymer Light-Emitting Devices for Passive-Matrix Flat Panel Displays”** *Ke Long<sup>1</sup>; Min-Hao Lu<sup>1</sup>;*  
 Florian Pschenitzka<sup>1</sup>; J. C. Sturm<sup>1</sup>; <sup>1</sup>Princeton University, Department of Electrical Engineering, Center for Photonics and Optoelectronic Materials (POEM), Princeton, NJ 08544 USA
- VI.B.-4 “Flexible Liquid Crystal Displays Driven by Organic Thin Film Transistors on Polymeric Substrates:** *C. D. Sheraw<sup>1</sup>; L. Zhou<sup>1</sup>;*  
 J. R. Huang<sup>1</sup>; L. Jia<sup>1</sup>; J. A. Nichols<sup>1</sup>; C. C. Kuo<sup>1</sup>; D. J. Gundlach<sup>1</sup>; T. N. Jackson<sup>1</sup>; M. G. Kane<sup>2</sup>; I. G. Hill<sup>2</sup>; M. S. Hammond<sup>2</sup>;  
 J. Campi<sup>2</sup>; B. K. Greening<sup>2</sup>; J. Franc<sup>3</sup>; J. West<sup>3</sup>; <sup>1</sup>The Pennsylvania State University, Center for Thin Film Devices, University Park, PA 16802 USA; <sup>2</sup>Sarnoff Corporation, Solid State Display Laboratory, Princeton, NJ 08543 USA; <sup>3</sup>Kent State University, Liquid Crystal Institute, Kent, OH 44242 USA

## SESSION VII.A. TFTs

183–196

- VII.A.-1 “Organic-Inorganic Electronic Devices Based on Hybrid Perovskites”** *D. B. Mitzi<sup>1</sup>; C. D. Dimitrakopoulos<sup>1</sup>; L. L. Kosbar<sup>1</sup>;*  
<sup>1</sup>IBM T. J. Watson Research Center, Yorktown Heights, NY 10598 USA
- VII.A.-2 “CMOS Polysilicon Circuits on Flexible Steel Substrates”** *Ming Wu<sup>1</sup>;* Sigurd Wagner<sup>1</sup>; <sup>1</sup>Princeton University, Department of Electrical Engineering, Princeton, NJ 08544 USA
- VII.A.-3 “High-Performance Thin-Film Transistor Fabricated on Poly-Si Films Prepared by Metal Imprint Technology”** *Kenji Makihira<sup>1</sup>;*  
 Masahito Yoshii<sup>1</sup>; Tanemasa Asano<sup>1</sup>; <sup>1</sup>Kyushu Institute of Technology, Center for Microelectronic Systems, 680-4 Kawazu, Iizuka, Fukuoka 820-8502, Japan
- VII.A.-4 “Excimer Laser Annealed, Poly-Si Thin Film Transistors for Flat Panel Imager Application”** *J. P. Lu<sup>1</sup>;* K. Van Schuylenbergh<sup>1</sup>;  
 J. Ho<sup>1</sup>; Y. Wang<sup>1</sup>; P. Nylén<sup>1</sup>; J. B. Boyce<sup>1</sup>; R. A. Street<sup>1</sup>; <sup>1</sup>Xerox Palo Alto Research Center, 3333 Coyote Hill Road, Palo Alto, CA 94304 USA
- VII.A.-5 “Amorphous Si TFTs on Plastically-Deformed Substrates with 3-D Shapes”** *P. I. Hsu<sup>1</sup>;* H. Gleskova<sup>1</sup>; Z. Suo<sup>1</sup>; S. Wagner<sup>1</sup>;  
 J. C. Sturm<sup>1</sup>; <sup>1</sup>Princeton University, Center for Photonics and Optoelectronic Materials (POEM), Princeton, NJ 08544 USA
- VII.A.-6 “Gate Control in Ultra-Short Channel Double-Gate MOSFETs Accounting for 2D and Quantum Confinement Effects”** *M. Mouis<sup>2</sup>;*  
 F.-N. Genin<sup>1</sup>; A. Poncet<sup>1</sup>; <sup>1</sup>Laboratoire de Physique de la Matière, UMR-CNRS n° 5511, INSA-Lyon 20, Avenue Albert Einstein, F-69621 Villeurbanne, France; <sup>2</sup>CEA-Grenoble, LETI/DTS/CPMA, 17 rue des Martyrs, 38054 Grenoble, Cedex 9 France

## SESSION VII.B. WIDE BANDGAP SEMICONDUCTORS

197–212

- VII.B.-1 “K-Band GaN Power HFET’s with 6.6 W/mm CW Saturated Output Power Density and 35% Power Added Efficiency at 20 GHz”** *Miro Micovic<sup>1</sup>;*  
 Jeong S. Moon<sup>1</sup>; Ara Kurdoghlian<sup>1</sup>; Paul Hashimoto<sup>1</sup>; Danny Wong<sup>1</sup>; Loren McCray<sup>1</sup>; Tahir Hussain<sup>1</sup>; Paul Janke<sup>1</sup>;  
<sup>1</sup>HRL Laboratories LLC, 3011 Malibu Canyon Road, Malibu, CA 90265 USA
- VII.B.-2 “Linearity of High Al-Content AlGaIn/GaN HEMTs”** *T. Jenkins<sup>1</sup>;* L. Kehias<sup>1</sup>; P. Parikh<sup>2</sup>; Y.-F. Wu<sup>2</sup>; P. Chavarkar<sup>2</sup>; M. Moore<sup>2</sup>;  
 U. Mishra<sup>2</sup>; <sup>1</sup>Air Force Research Laboratory, 2241 Avionics Circle, Wright-Patterson AFB, OH 45433 USA; <sup>1</sup>Cree Lighting Company, 340 Storke Road, Goleta, CA 93117 USA
- VII.B.-3 “Demonstration of Push-Pull Operation of AlGaIn/GaN HEMTs on SiC”** *Jong-Wook Lee<sup>1</sup>;* Sungjae Lee<sup>1</sup>; Keven J. Webb<sup>1</sup>;  
<sup>1</sup>Purdue University, School of Electrical and Computer Engineering, West Lafayette, IN 47907 USA
- VII.B.-5 “An X-Band Silicon Carbide IMPATT Diode”** *Luo Yuan<sup>1</sup>;* Michael R. Melloch<sup>1</sup>; James A. Cooper, Jr.<sup>1</sup>; Kevin J. Webb<sup>1</sup>;  
<sup>1</sup>Purdue University, School of Electrical and Computer Engineering, West Lafayette, IN 47907 USA
- VII.B.-6 “The Effect of Emitter Implant and Anneal on High-Voltage 4H-SiC BJTs”** *Yi Tang<sup>1</sup>;* Jeffrey B. Fedison<sup>1</sup>; T. Paul Chow<sup>1</sup>;  
<sup>1</sup>Rensselaer Polytechnic Institute, Center for Integrated Electronics and Electronic Manufacturing, Troy, NY 12180 USA
- VII.B.-7 “Diamond Surface Channel FET with  $f_{max}$  Above 30 GHz”** *A. Aleksov<sup>1</sup>;* A. Denisenko<sup>1</sup>; U. Spitzberg<sup>1</sup>; E. Kohn<sup>1</sup>;  
<sup>1</sup>University of Ulm, Dept. of Electron Devices and Circuits, Albert-Einstein-Allee 45, D-89081 Ulm, Germany

# Plenary Session

**MONDAY AM, JUNE 25<sup>TH</sup>, 2001**

*Session Organizer:* Sanjay Banerjee, The University of Texas at Austin

*Session Chair:* Mark Rodwell, University of California at Santa Barbara

**8:30 AM, Welcoming Remarks**

**Plenary Speakers:**

**9:00 AM, I.1 Invited**

**SOI and Nanoscale MOSFETs:** *Chenming Hu*<sup>1</sup>; <sup>1</sup>University of California, Department of Electrical Engineering and Computer Sciences, Berkeley, CA 94720 USA

**9:40 AM, I.2 Invited**

**Vertical Cavity Surface Emitting Laser - Exploratory, Emerging, or Disruptive?:** *K. Iga*<sup>1</sup>; <sup>1</sup>Tokyo Institute of Technology, 4259 Nagatsuta, Midoriku, Yokohama 226-8502 Japan

**10:20 AM Break**

**10:45 AM, I.3 Invited**

**Low-Noise, High-Speed Avalanche Photodiodes:** *Joe C. Campbell*<sup>1</sup>; <sup>1</sup>The University of Texas at Austin, Microelectronics Research Center, 10100 Burnet Road, Mail Code R9950, Austin, TX 78712 USA

**11:25 AM, I.4 Invited**

**Status, Prospects and Commercialization of SiC Power Devices:** *Dietrich Stephani*<sup>1</sup>; <sup>1</sup>SiCED Electronics Development GmbH & Co. KG, Paul-Gossen-Str. 100, D91052 Erlangen, Germany



## Silicon Devices

MONDAY PM, JUNE 25<sup>TH</sup>, 2001

*Session Organizer:* Jeffrey Welser, IBM Technology Group

**2:00 PM, II.A.-1, Invited**

**High-K Gate Dielectrics for Sub-100 nm CMOS Technology:** *Dim-Lee Kwong*<sup>1</sup>; <sup>1</sup>The University of Texas at Austin, Microelectronics Research Center, 10100 Burnet Road, Bldg. 160, Austin, TX 78758 USA

**2:30 PM, II.A.-2**

**Fast Write Time and Long Retention 1T Memory:** *Albert Chin*<sup>1</sup>; M. Y. Yang<sup>1</sup>; S. B. Chen<sup>1</sup>; C. L. Sun<sup>2</sup>; S. Y. Chen<sup>2</sup>; <sup>1</sup>National Chiao Tung University, Dept. of Electronics Engineering, Hsinchu, Taiwan; <sup>2</sup>National Chiao Tung University, Dept. of Materials Science Engineering, Hsinchu, Taiwan

**2:50 PM, II.A.-3**

**Physical Origin of SILC and Noisy Breakdown in Very Thin Silicon Nitride Gate Dielectric:** *Igor Polishchuk*<sup>1</sup>; Tsu-Jae King<sup>1</sup>; Chenming Hu<sup>1</sup>; <sup>1</sup>University of California at Berkeley, Department of Electrical Engineering and Computer Sciences, Berkeley, CA 94720 USA

**3:10 PM, II.A.-4**

**Low-Power CMOS at  $V_{dd}=4kT/q$ :** *Andres Bryant*<sup>1</sup>; Jeffrey Brown<sup>1</sup>; Peter Cottrell<sup>1</sup>; Mark Ketchen<sup>2</sup>; John Ellis-Monaghan<sup>1</sup>; E. J. Nowak<sup>1</sup>; <sup>1</sup>IBM Microelectronics Division, Essex Junction, VT 05452 USA; <sup>2</sup>IBM T. J. Watson Research Center, Yorktown Heights, NY 10598 USA

**3:30 PM Break**

**3:50 PM, II.A.-5**

**A Sub-40nm Body Thickness N-Type FinFET:** *David M. Fried*<sup>1</sup>; Arthur P. Johnson<sup>1</sup>; Edward J. Nowak<sup>1</sup>; Jed H. Rankin<sup>1</sup>; Christa R. Willets<sup>1</sup>; <sup>1</sup>IBM Microelectronics Division, Essex Junction, VT 05452 USA

**4:10 PM, II.A.-6**

**Quasi-Planar NMOS FinFETs with Sub-100nm Gate Lengths:** *Nick Lindert*<sup>1</sup>; Yang-Kyu Choi<sup>1</sup>; Leland Chang<sup>1</sup>; Erik Anderson<sup>2</sup>; Wenchin Lee<sup>3</sup>; Tsu-Jae King<sup>1</sup>; Jeffrey Bokor<sup>1</sup>; Chenming Hu<sup>1</sup>; <sup>1</sup>University of California at Berkeley, Department of Electrical Engineering and Computer Sciences, Berkeley, CA 94709 USA; <sup>2</sup>X-Ray Optics, Lawrence Berkeley National Laboratory, Berkeley, CA USA; <sup>3</sup>Intel Corporation, Logic Technology Development, Hillsboro, OR USA

**4:30 PM, II.A.-7**

**High Performance of Planar Double Gate MOSFETs with Thin Backgate Dielectrics:** *Erin C. Jones*<sup>1</sup>; Meikei Jeong<sup>2</sup>; Thomas Kanarsky<sup>2</sup>; Omer Dokumaci<sup>2</sup>; Ronnen A. Roy<sup>1</sup>; Leathen Shi<sup>1</sup>; Toshiharu Furukawa<sup>3</sup>; Robert J. Miller<sup>1</sup>; H-S Philip Wong<sup>1</sup>; <sup>1</sup>IBM T. J. Watson Research Center, Yorktown Heights, NY 10598 USA; <sup>2</sup>IBM SRDC, Hopewell Junction, NY 12533 USA; <sup>3</sup>IBM Microelectronics Division, Essex Junction, VT 05254 USA

**4:50 PM, II.A.-8**

**$Si_{1-x}Ge_x$  Channel Vertical PMOSFET with Asymmetric Ge Profile:** *Xiangdong Chen*<sup>1</sup>; Qiqing Ouyang<sup>1</sup>; Sankaran Kartik Jayanarayanan<sup>1</sup>; Freek E. Prins<sup>1</sup>; Sanjay Banerjee<sup>1</sup>; <sup>1</sup>The University of Texas at Austin, Microelectronics Research Center, 10100 Burnet Road, Bldg. 160, Austin, TX 78758 USA

## III-V Devices and Sources

**MONDAY PM, JUNE 25<sup>TH</sup>, 2001**

*Session Organizer:* Colombo Bolognesi, Simon Fraser University

**2:00 PM, II.B.-1 Invited**

**Optical Interconnections to Silicon Integrated Circuits:** *David Miller*<sup>1</sup>; <sup>1</sup>Stanford University, Stanford, CA 94305 USA

**2:30 PM, II.B.-2**

**Temperature-Dependent Large Signal Modulation and Auger Recombination in In<sub>0.4</sub>Ga<sub>0.6</sub>As Quantum-Dot Lasers:** *S. Ghosh*<sup>1</sup>; P. Bhattacharya<sup>1</sup>; E. Stoner<sup>1</sup>; H. Jiang<sup>2</sup>; S. Nuttinck<sup>3</sup>; J. Singh<sup>1</sup>; J. Laskar<sup>3</sup>; <sup>1</sup>University of Michigan, Solid State Electronics Laboratory, Department of Electrical Engineering and Computer Science, Ann Arbor, MI 48109 USA; <sup>2</sup>Broadcom Corporation, 16215 Alton Parkway, Irvine, CA 92619 USA; <sup>3</sup>Georgia Institute of Technology, Microelectronics Research Center, Department of Electrical Engineering, Atlanta, GA 30332 USA

**2:50 PM, II.B.-3**

**ZnSe-Based Laser Diodes for the 560 nm Spectral Region:** *M. Klude*<sup>1</sup>; G. Alexe<sup>1</sup>; C. Kruse<sup>1</sup>; T. Passow<sup>1</sup>; D. Hommel<sup>1</sup>; <sup>1</sup>Institut für Festkörperphysik, Universität Bremen, 28359 Bremen, Germany

**3:10 PM, II.B.-4**

**NpN InGaAsN-Based Heterojunction Bipolar Transistors with  $f_{max} = 60\text{GHz}$ :** *C. Monier*<sup>1</sup>; A. G. Baca<sup>1</sup>; F. Newman<sup>2</sup>; P. C. Chang<sup>1</sup>; N. Y. Li<sup>2</sup>; H. Q. Hou<sup>2</sup>; E. Armour<sup>3</sup>; R. Stall<sup>3</sup>; <sup>1</sup>Sandia National Laboratories, Albuquerque, NM 87185 USA; <sup>2</sup>Emcore Corporation, Emcore Photovoltaics, Albuquerque, NM 87123 USA; <sup>3</sup>Emcore Corporation, Sommerset, NJ 08873 USA

**3:30 PM Break**

**3:50 PM, II.B.-5**

**Noise Characteristics of Highly Strained InGaP/InGaAs p-HEMTs Grown on Patterned Substrates by Using Compound-Source MBE:** *Jeong Hoon Kim*<sup>1</sup>; Sung-June Jo<sup>1</sup>; Jong-In Song<sup>1</sup>; <sup>1</sup>K-JIST, Department of Information and Communications, 1 Oryong-dong Buk-gu, Kwangju, 500-712 Korea

**4:10 PM, II.B.-6**

**A Flip-Flop Based on Monolithic Integration of InAs/AlSb/GaSb RITDs and InAlAs/InGaAs/InP HEMTs:** *P. Fay*<sup>1</sup>; Y. Xu<sup>1</sup>; G. H. Bernstein<sup>1</sup>; A. Gonzalez<sup>2</sup>; P. Mazumder<sup>2</sup>; D. H. Chow<sup>3</sup>; J. N. Schulman<sup>3</sup>; <sup>1</sup>University of Notre Dame, Department of Electrical Engineering, Notre Dame, IN 46556 USA; <sup>2</sup>University of Michigan, Department of Electrical Engineering and Computer Science, Ann Arbor, MI 48109 USA; <sup>3</sup>HRL Laboratories, Malibu, CA 90265 USA

**4:30 PM, II.B.-7**

**Monolithic Integration of InAlAs/InGaAs Enhancement and Depletion (E/D)-Mode Metamorphic HEMTs on GaAs Substrate:** *D. C. Dumka*<sup>1</sup>; W. E. Hoke<sup>2</sup>; P. J. Lemonias<sup>2</sup>; R. Schwind<sup>1</sup>; G. Cueva<sup>1</sup>; I. Adesida<sup>1</sup>; <sup>1</sup>University of Illinois at Urbana-Champaign, Microelectronics Laboratory, Department of Electrical and Computer Engineering, 208 Wright Street, Urbana, IL 61801 USA; <sup>2</sup>Raytheon RF Components, 362 Lowell Street, Andover, MA 01810 USA

MONDAY PM, JUNE 25<sup>TH</sup>, 2001, 5:30 PM–8:00 PM

**III.-1–Dual-Channel SOI LIGHT with Improved Latch-Up and Forward Voltage Drop Characteristics:** *Woo-Beom Choi*<sup>1</sup>; Woong-Je Sung<sup>1</sup>; Yong-Il Lee<sup>1</sup>; Man Young Sung<sup>1</sup>; <sup>1</sup>Korea University, Dept. of Elect. Eng., 1, 5-ka, Anam-dong, Sungbuk-ku, Seoul 136-701 Korea

**III.-2–Chaos Generator MMIC's Using Resonant Tunneling Diodes:** *K. Maezawa*<sup>1</sup>; Y. Kawano<sup>1</sup>; Y. Ohno<sup>1</sup>; S. Kishimoto<sup>1</sup>; T. Mizutani<sup>1</sup>; <sup>1</sup>Nagoya University, Graduate Sch. of Eng., Furo-cho, Chikusa-ku, Nagoya-shi, 464-8603 Japan

**III.-3–High Detectivity Solar Blind AlGaIn Metal-Semiconductor-Metal Detector:** *Jean-Luc Reverchon*<sup>1</sup>; Jean-Yves Duboz<sup>1</sup>; Fabrice Semond<sup>2</sup>; Nicolas Grandjean<sup>2</sup>; Jean Massies<sup>2</sup>; <sup>1</sup>Laboratoire Central de Recherches, THALES, 91404 ORSAY, Cedex, France; <sup>2</sup>CRHEA-CNRS, rue Bernard Gregory, Sophia Antipolis 06560 Valbonne, France

**III.-4–Characterization of a 0.1  $\mu\text{m}$  MOSFET Using Cross-Sectional Scanning Tunneling Microscopy:** *T. Okui*<sup>1</sup>; S. Hasegawa<sup>1</sup>; H. Nakashima<sup>1</sup>; H. Fukutome<sup>2</sup>; H. Arimoto<sup>2</sup>; <sup>1</sup>Osaka University, The Institute of Scientific and Industrial Research, 8-1 Mihogaoka, Ibaraki, Osaka 567-0047 Japan; <sup>2</sup>Fujitsu Laboratories Ltd., 10-1 morinosato-wakamiya, Atsugi, Kanagawa 243-0197 Japan

**III.-5–Nanoscale MOSFETs Scaling:** *Yehuda Naveh*<sup>1</sup>; Victor Sverdlov<sup>1</sup>; Konstantin Likharev<sup>1</sup>; <sup>1</sup>State University of New York, Stony Brook, NY 11794-3800 USA

**III.-6–50 nm Vertical Surround Gate MOSFET with S-Factor of 75mV/dec:** *Ruigang Li*<sup>1</sup>; Yaohui Zhang<sup>2</sup>; Yang Lu<sup>2</sup>; Daniel Sung Choi<sup>2</sup>; Marie Luo<sup>3</sup>; Kang L. Wang<sup>2</sup>; <sup>1</sup>University of California at Los Angeles, Elect. Eng. Dept., Rm. 56-125B ENGR IV, Los Angeles, CA 90095-1594 USA; <sup>2</sup>University of California at Los Angeles, Elect. Eng. Dept., Los Angeles, CA 90095-1594 USA; <sup>3</sup>Conexant Systems, Inc., 4311 Jamboree, Newport Beach, CA 92660 USA

**III.-7–Hyperspectral Imaging of Breakdown in InAlAs/InGaAs HEMTs: A Comparative Study:** *Mark Somerville*<sup>1</sup>; Jon Rameau<sup>1</sup>; Nii Moi Addo<sup>1</sup>; <sup>1</sup>Vassar College, Dept. of Phys. and Astron., 124 Raymond Ave., Poughkeepsie, NY 12604 USA

**III.-8–Extension of Safe-Operating-Area by Optimizing Body-Current in Submicron LDMOS Transistors:** *S. K. Lee*<sup>1</sup>; Y. C. Choi<sup>1</sup>; J. H. Kim<sup>1</sup>; C. J. Kim<sup>1</sup>; H. S. Kang<sup>1</sup>; C. S. Song<sup>1</sup>; <sup>1</sup>Fairchild Korea Semiconductor Co. New Techn. Devel. Team, 82-3 Dodang-Dong, Wonmi-Ku, Puchon, Kyonggi-Do, Korea

**III.-9–Computer Analysis of Geometry and Strain Effects in Silicon Nano-Crystal Floating-Gate Flash Memory Devices:** *Aaron Thean*<sup>1</sup>; Jean-Pierre Leburton<sup>1</sup>; <sup>1</sup>University of Illinois, Beckman Institute for Advanced Science & Technology, Dept. of Elec. & Comp. Eng., Urbana, IL 61801 USA

**III.-10–An Extension of McKelvey's One-Flux Method to Energy Space:** *W. R. McKinnon*<sup>1</sup>; <sup>1</sup>National Research Council, Ottawa, K1A 0R6, Canada

**III.-11–Characterization of Midgap Tungsten Gate MOSFETs:** *Huiling Shang*<sup>1</sup>; Marvin H. White<sup>1</sup>; Kathryn W. Gaurini<sup>2</sup>; Edward Cartier<sup>2</sup>; Paul Solomon<sup>2</sup>; <sup>1</sup>Lehigh University, EECS Dept., Sherman Fairchild Lab., Bethlehem, PA 18015 USA; <sup>2</sup>IBM T. J. Watson Research Center, PO Box 218, Yorktown Heights, NY 10598 USA

**III.-12–ESD Protection for High Voltage LDMOS with Sense FET:** *Y. S. Choi*<sup>1</sup>; J. J. Kim<sup>1</sup>; C. K. Jeon<sup>1</sup>; M. H. Kim<sup>1</sup>; S. L. Kim<sup>1</sup>; H. S. Kang<sup>1</sup>; C. S. Song<sup>1</sup>; <sup>1</sup>Fairchild Semiconductor, Process R&D Group, 82-3 Dodang-Dong, Wonmi-Ku, Puchon, Kyonggi-Do, 420-711, Korea

**III.-13–Mixed Mode Double-Gate FET Model:** *P. M. Solomon*<sup>1</sup>; <sup>1</sup>IBM T. J. Watson Research Center, Yorktown Heights, NY 10598 USA

**III.-14–Low Programming Voltages and Long Retention Time in Metal Nanocrystal EEPROM Devices:** *Zengtao Liu*<sup>1</sup>; Venkat

Narayanan<sup>1</sup>; Myongseob Kim<sup>1</sup>; Gen Pei<sup>1</sup>; Edwin C. Kan<sup>1</sup>; <sup>1</sup>Cornell University, Elect. and Comp. Eng., Ithaca, NY 14853 USA

**III.-15–High Performance AlGaIn/GaN HEMTs with Recessed Gate on Sapphire Substrate:** *Y. Sano*<sup>1</sup>; T. Yamada<sup>1,2</sup>; J. Mita<sup>1,2</sup>; K. Kaifu<sup>1</sup>; H. Ishikawa<sup>3</sup>; T. Egawa<sup>3</sup>; M. Umeno<sup>3</sup>; <sup>1</sup>Oki Electric Industry Co., Ltd., Corp. Res. Lab., 550-5 Higashiawakawa, Hachioji, Tokyo 193-8550 Japan; <sup>2</sup>Ultra-Low-Loss Power Device Technology Research Body; <sup>3</sup>Nagoya Institute of Technology, Gokiso-cho, Showa-ku, Nagoya 466-8555 Japan

**III.-16–A Comparison of Bulk and SOI Deep Sub-Micron MOSFET Small-Signal Behavior in the High-Frequency Regime Beyond 10GHz:** *D. Goldman*<sup>1</sup>; T. Gafron<sup>1</sup>; C.-S. Kim<sup>1</sup>; Q. Nguyen<sup>1</sup>; F. Burke<sup>1</sup>; B. Cheek<sup>1</sup>; S. Parke<sup>1</sup>; <sup>1</sup>Boise State University, Dept. of Elect. and Comp. Eng., Boise, ID 83725 USA

**III.-17–Threshold Voltage Shift by Quantum Confinement in Ultra-Thin Body Device:** *Yang-Kyu Choi*<sup>1</sup>; Daewon Ha<sup>1</sup>; Tsu-Jae King<sup>1</sup>; Chenming Hu<sup>1</sup>; <sup>1</sup>University of California at Berkeley, Dept. of Elect. Eng. and Comp. Scis., Berkeley, CA 94720 USA

**III.-18–A New and Accurate Quantum Mechanical Compact Model for NMOS Gate Capacitance:** *S. Mudanai*<sup>1</sup>; L. F. Register<sup>1</sup>; A. F. Tasch<sup>1</sup>; S. K. Banerjee<sup>1</sup>; <sup>1</sup>The University of Texas at Austin, Microel. Res. Ctr., Mail Code R9950, Austin, TX 78712 USA

**III.-19–An Intrinsically Coupled HBT/RTD Device Enabling an Adjustable Peak-Current-Density:** *P. Velling*<sup>1</sup>; M. Agethen<sup>1</sup>; W. Prost<sup>1</sup>; G. Janssen<sup>2</sup>; R. M. Bertenburg<sup>2</sup>; F. J. Tegude<sup>1</sup>; <sup>1</sup>Gerhard-Mercator University, Solid State Electr. Dept., 47057 Duisburg, Germany; <sup>2</sup>IPAG-Innovative Processing AG, Lotharstrasse 55 (ZHO), 47057 Duisburg, Germany

**III.-20–Excellent DC Characteristics of HEMTs on Semi-Insulating Silicon Carbide Substrate:** *S. Arulkumaran*<sup>1</sup>; T. Egawa<sup>1</sup>; G. Zhao<sup>1</sup>; H. Ishikawa<sup>1</sup>; M. Umeno<sup>1</sup>; <sup>1</sup>Nagoya Institute of Technology, Research Center for Micro-Structure Devices, Gokiso-cho, Showa-ku, Nagoya 466-8555 Japan

**III.-21–A Quantum Dot FET–A Future Playground of Quantum State Manipulation:** *Kanji Yoh*<sup>1</sup>; Hironobu Kazama<sup>1</sup>; Yoshito Katano<sup>1</sup>; <sup>1</sup>Hokkaido University, Res. Center for Interface Quant. Elect., N 13, W8, Kita-ku, Sapporo, Hokkaido 060-8628 Japan

**III.-22–Sub-40nm V-Groove MOSFETs:** *J. Appenzeller*<sup>1</sup>; R. Martell<sup>1</sup>; Ph. Avouris<sup>1</sup>; J. Knoch<sup>2</sup>; Y. Lu<sup>3</sup>; K. L. Wang<sup>3</sup>; J. Scholvin<sup>4</sup>; J. A. del Alamo<sup>4</sup>; P. Rice<sup>5</sup>; P. Solomon<sup>1</sup>; <sup>1</sup>IBM T. J. Watson Research Center, Yorktown Heights, NY 10598 USA; <sup>2</sup>II. Physikalisches Institut, RWTH Aachen, Templergraben 55, 52056 Aachen, Germany; <sup>3</sup>University of California at Los Angeles, Los Angeles, CA 90095 USA; <sup>4</sup>Massachusetts Institute of Technology, 77 Massachusetts Ave., Cambridge, MA 02139 USA; <sup>5</sup>IBM Almaden Research Center, San Jose, CA 95120 USA

**III.-23–Terahertz Plasma-Wave Excitation in 80-nm Gate-Length GaAs MESFET by Photomixing Long-Wavelength CW Laser Sources:** *Taiichi Otsuji*<sup>1</sup>; Yoshihiro Kanamaru<sup>1</sup>; Hajime Kitamura<sup>1</sup>; Shin Nakae<sup>1</sup>; <sup>1</sup>Kyushu Institute of Technology, Dept. of Control Sci. and Eng., Iizuka, Fukuoka, 820-8502 Japan

**III.-24–Fabrication of InP DHBTs with 0.1 $\mu\text{m}$  Wide Emitter:** *T. Arai*<sup>1</sup>; H. Nagatsuka<sup>1</sup>; Y. Miyamoto<sup>1</sup>; K. Furuya<sup>1</sup>; <sup>1</sup>Tokyo Institute of Technology, Dept. of Phys. Electr., 2-12-1 O-okayama, Meguro-ku, Tokyo 152-8552 Japan

**III.-25–Characteristics of Submicron HBTs in the 140-220 GHz Band:** *M. Urteaga*<sup>1</sup>; D. Scott<sup>1</sup>; T. Matthew<sup>1</sup>; S. Krishnan<sup>1</sup>; Y. Wei<sup>1</sup>; M. Dahlstrom<sup>1</sup>; M. Rodwell<sup>1</sup>; <sup>1</sup>University of California at Santa Barbara, Dept. of ECE, Santa Barbara, CA 93106 USA

**III.-26–A Quantum-Dot Cellular Automata Shift Register:** *Ravi Kummmamaru*<sup>1</sup>; Aexei O. Orlov<sup>1</sup>; John P. Timler<sup>1</sup>; R. Ramasubramaniam<sup>1</sup>; Craig S. Lent<sup>1</sup>; Gary H. Bernstein<sup>1</sup>; Gregory L. Snider<sup>1</sup>; <sup>1</sup>University of Notre Dame, Dept. of Elect. Eng., Notre Dame, IN 46556 USA

## Emerging Technologies

TUESDAY AM, JUNE 26<sup>TH</sup>, 2001

*Session Organizer:* Sanjay Banerjee, The University of Texas at Austin

### 9:00 AM, IV.-1 Invited

**Nanotube Nanoelectronics:** *Paul L. McEuen*<sup>1, 2</sup>; J. Park<sup>2, 3</sup>; A. Bachtold<sup>2, 3</sup>; M. Woodside<sup>2, 3</sup>; M. S. Fuhrer<sup>2, 3</sup>; M. Bockrath<sup>2, 3</sup>; L. Shi<sup>4</sup>; A. Majumdar<sup>4</sup>; P. Kim<sup>2, 3</sup>; <sup>1</sup>Cornell University, Laboratory of Atomic and Solid State Physics, Ithaca, NY 14853 USA; <sup>2</sup>University of California, Department of Physics, Berkeley, CA 94720 USA; <sup>3</sup>University of California, Materials Sciences Division, Lawrence Berkeley National Laboratory, Berkeley, CA 94720 USA; <sup>4</sup>University of California, Department of Mechanical Engineering, Berkeley, CA 94720 USA

### 9:30 AM, IV.-2 Invited

#### **Molecule/Metal and Molecule/Semiconductor**

**Heterostructures for Electronic Devices:** *David B. Janes*<sup>1</sup>; Purdue University, School of Electrical and Computer Engineering, W. Lafayette, IN 47907 USA

### 10:00 AM, IV.-3 Invited

#### **Integrated RF Passive Components - Discrete vs. Distributed:**

*J. N. Burghartz*<sup>1</sup>; K. T. Ng<sup>1</sup>; N. P. Pham<sup>1</sup>; B. Rejaei<sup>1</sup>; P. Sarro<sup>1</sup>; <sup>1</sup>Delft University of Technology, EC TM-DIMES, Feldmannweg 17, 2600 GB Delft, The Netherlands

### 10:30 AM Break

### 10:50 AM, IV.-4 Invited

#### **Photonic Crystal Cavities and Waveguides:**

*A. Scherer*<sup>1</sup>; O. Painter<sup>1</sup>; J. Vuckovic<sup>1</sup>; M. Loncar<sup>1</sup>; D. Dapkus<sup>2</sup>; I. Kim<sup>2</sup>; T. Pearsall<sup>3</sup>; <sup>1</sup>Caltech, MC 200-36, Pasadena, CA 91125 USA; <sup>2</sup>University of Southern California; <sup>3</sup>CERF Corning, Avon France

### 11:20 AM, IV.-5 Invited

#### **Electronic Detection of DNA: Robust Platform for Integrated**

**Devices:** *Robert H. Terbrueggen*<sup>1</sup>; Yin-Peng Chen<sup>1</sup>; Hau Duong<sup>1</sup>; Dan Farkas<sup>1</sup>; K. M. Millan<sup>1</sup>; Gary T. Olsen<sup>1</sup>; Nathan Swami<sup>1</sup>; Hai Wang<sup>1</sup>; Handy Yowanto<sup>1</sup>; C. J. Yu<sup>1</sup>; Gary F. Blackburn<sup>1</sup>; Jon Faiz Kayyem<sup>1</sup>; <sup>1</sup>Motorola Clinical Micro Sensors, 757 South Raymond Avenue, Pasadena, CA 91105 USA

## Novel Devices

**TUESDAY PM, JUNE 26TH, 2001**

*Session Organizers:* Rick Kiehl, University of Minnesota

### 2:00 PM, V.A.-1 Invited

**Tunable Two-Electron Spin States in Quantum Dot Structures and the Applicability for Making Spin Qubits:** *S. Tarucha<sup>1,3</sup>; K. Ono<sup>2</sup>; D. G. Austing<sup>3</sup>; S. Sasaki<sup>3</sup>; T. Fujisawa<sup>3</sup>; Y. Tokura<sup>3</sup>; L. P. Kouwenhoven<sup>4</sup>; <sup>1</sup>ERATO Mesoscopic Correlation Project & <sup>2</sup>Department of Physics, University of Tokyo, 7-3-1 Bunkyo-ku, Hongo, 7-3-1 Tokyo 113-0033, Japan; <sup>3</sup>NTT Basic Research Laboratories, Morinosato Wakamiya, Atugi-shi, Kanagawa 243-0198, Japan; <sup>4</sup>ERATO Mesoscopic Correlation Project, & Department of Applied Physics, Delft University of Technology, P.O. Box 5046, 2600 GA Delft, The Netherlands*

### 2:30 PM, V.A.-2

**A Multiple-Valued SRAM with Combined Single-Electron and MOS Transistors:** *Hiroshi Inokawa<sup>1</sup>; Akira Fujiwara<sup>1</sup>; Yasuo Takahashi<sup>1</sup>; <sup>1</sup>NTT Basic Research Laboratories, 3-1 Morinosato Wakamiya, Atsugi-shi, Kanagawa Pref., 243-0198 Japan*

### 2:50 PM, V.A.-3

**Binary-Decision-Diagram Quantum Circuits Based on Schottky Wrap Gate Control of GaAs Honeycomb Nanowires:** *Seiya Kasai<sup>1</sup>; Hideki Hasegawa<sup>1</sup>; <sup>1</sup>Hokkaido University, Research Center for Interface Quantum Electronics and Graduate School of Electronics and Information Engineering, N-13, W-8, Kita-ku, Sapporo 060-8628 Japan*

### 3:10 PM, V.A.-4

**Single Electron Transistors with Sidewall Depletion Gates on a Silicon-On-Insulator Quantum Wire:** *D. H. Kim<sup>1</sup>; K. R. Kim<sup>1</sup>; S.-K. Sung<sup>1</sup>; B. H. Choi<sup>2&3</sup>; S. W. Hwang<sup>2&3</sup>; D. Ahn<sup>2</sup>; J. D. Lee<sup>1</sup>; B.-G. Park<sup>1</sup>; <sup>1</sup>Seoul National University, Inter-University Semiconductor Research Center (ISRC) and School of Electrical Engineering, San 56-1, Shinlim-dong, Kwanak-gu, Seoul 151-742, Korea; <sup>2</sup>University of Seoul, Institute of Quantum Information Processing and Systems (iQUIPS), Seoul 130-743, Korea; <sup>3</sup>Korea University, School of Electrical Engineering, Anamdong, Sungbukku, Seoul 136-701 Korea*

### 3:30 PM Break

### 3:50 PM, V.A.-5

**A Semiconductor GMR Device:** *Kanji Yoh<sup>1</sup>; T. Doi<sup>1</sup>; Y. Katano<sup>1</sup>; S. Abe<sup>2</sup>; H. Ohno<sup>2</sup>; K. Sueoka<sup>2</sup>; K. Mukasa<sup>2</sup>; <sup>1</sup>Hokkaido University, Research Center for Interface Quantum Electronics, N 13, W8, Kita-ku, Sapporo, Hokkaido 060-8628 Japan; <sup>2</sup>Hokkaido University, Graduate School of Electronics and Information Technology, N 13, W8, Kita-ku, Sapporo, Hokkaido 060-8628 Japan*

### 4:10 PM, V.A.-6

**Digital Thin Film Non-Volatile Optical Memory:** *Robert C. J. Chi<sup>1</sup>; A. J. Steckl<sup>1</sup>; <sup>1</sup>University of Cincinnati, Nanoelectronics Laboratory, Cincinnati, OH 45221-0030 USA*

### 4:30 PM, V.A.-7

**Modeling and Design Study of Nanocrystal Memory Devices:** *Min-She<sup>1</sup>; Ya-Chin King<sup>2</sup>; Tsu-Jae King<sup>1</sup>; Chenming Hu<sup>1</sup>; <sup>1</sup>University of California at Berkeley, Department of Electrical Engineering and Computer Sciences, Berkeley, CA 94720 USA; <sup>2</sup>National Tsing-Hua University, Department of Electrical Engineering, Hsinchu, Taiwan*

### 4:50 PM, V.A.-8

**Quasi-Magnetic Fields Revisited: Second-Order Transport Effects in Graded Semiconductors:** *William R. Frensley<sup>1</sup>; <sup>1</sup>University of Texas at Dallas, Richardson, TX 75083 USA*

## Detectors

TUESDAY PM, JUNE 26<sup>TH</sup>, 2001

*Session Organizer:* Pallab Bhattacharya, University of Michigan

### 2:00 PM, V.B.-1 Invited

**Single Electron Transistors as Far-Infrared Photon Detectors:** *O. Astafiev*<sup>1</sup>; V. Antonov<sup>1</sup>; T. Kutsuwa<sup>1</sup>; S. Komiyama<sup>2</sup>; <sup>1</sup>Department of Basic Science, University of Tokyo, Komaba 3-8-1, Meguro-ku, Tokyo 153-8902, Japan; <sup>2</sup>Japan Science and Technology Corporation (JST)

Kawaguchi-shi, Saitama 332-0012, Japan

### 2:30 PM, V.B.-2

**High-Speed Waveguide Avalanche Photodetectors:** *Geoffrey Kinsey*<sup>1</sup>; R. Sidhu<sup>1</sup>; A. L. Holmes, Jr.<sup>1</sup>; J. C. Campbell<sup>1</sup>; <sup>1</sup>The University of Texas at Austin, Microelectronics Research Center, MER 1.608B/R9900, Austin, TX 78712 USA

### 2:50 PM, V.B.-3

**200-Gbit/s Monolithic Photodiode-Electroabsorption Modulator (PD-EAM) Optical Gate:** *S. Kodama*<sup>1</sup>; T. Ito<sup>1</sup>; N. Watanabe<sup>1</sup>; S. Kondo<sup>1</sup>; H. Takeuchi<sup>1</sup>; H. Ito<sup>1</sup>; T. Ishibashi<sup>1</sup>; <sup>1</sup>NTT Photonics Laboratories, Morinsato-Wakamiya 3-1, Atsugi-shi, Kanagawa 243-0198, Japan

### 3:10 PM, V.B.-4

**A CMOS-Compatible High-Speed Silicon Lateral Trench Photodetector:** *Min Yang*<sup>2</sup>; Ken Rim<sup>1</sup>; Dennis Rogers<sup>1</sup>; Jeremy Schaub<sup>1</sup>; Jeffrey Welsler<sup>1</sup>; Daniel Kuchta<sup>1</sup>; Diane Boyd<sup>2</sup>; <sup>1</sup>IBM T. J. Watson Research Center, P. O. Box 218, Yorktown Heights, NY 10598 USA; <sup>2</sup>IBM Microelectronics, Hopewell Junction, NY 12533 USA

### 3:30 PM Break

### 3:50 PM, V.B.-5

**High-Temperature Operation of Mid-Infrared ( $\lambda=4\text{-}5\mu\text{m}$ ) Vertical and Lateral InAs/GaAs/AlGaAs Quantum Dot Infrared Photodetectors:** *A. D. Stiff*<sup>1</sup>; S. Krishna<sup>1</sup>; P. Bhattacharya<sup>1</sup>; S. Kennerly<sup>1</sup>; <sup>1</sup>University of Michigan, Solid State Electronics Laboratory, Department of Electrical Engineering and Computer Science, Ann Arbor, MI 48109-2122 USA; <sup>2</sup>Army Research Laboratory, Sensors and Electron Devices Directorate, Adelphi, MD 20783 USA

### 4:10 PM, V.B.-6

**Normal-incident  $\text{In}_{0.2}\text{Ga}_{0.8}\text{As}/\text{GaAs}$  Quantum Well Infrared Photodetector Employing a p-i-n-i-p Camel Diode Structure:** *Heesoo Son*<sup>1</sup>; Jinsung Park<sup>1</sup>; Songcheol Hong<sup>1</sup>; Sung-June Jo<sup>2</sup>; Jong-In Song<sup>2</sup>; <sup>1</sup>KAIST, Department of Electrical Engineering and Computer Science, Taejon 305-701, Korea; <sup>2</sup>K-JIST, Department of Information and Communications, Kwangju 500-712, Korea

### 4:30 PM, V.B.-7

**High Efficiency, Large Area, InGaAs/InPAs Thermophotovoltaic Cells:** *R. R. Siegie*<sup>1</sup>; B. Wernsman<sup>1</sup>; S. A. Derry<sup>1</sup>; R. J. Wehrer<sup>1</sup>; S. D. Link<sup>1</sup>; M. N. Palmisiano<sup>1</sup>; D. R. Riley<sup>1</sup>; C. S. Murray<sup>2</sup>; F. Newman<sup>2</sup>; J. Hills<sup>2</sup>; <sup>1</sup>Bechtel Bettis, Inc., 814 Pittsburgh-McKeesport Blvd, West Mifflin, Pennsylvania 15122; <sup>2</sup>Emcore Photovoltaics, Albuquerque, NM 87123 USA

## Nanostructure Modeling

WEDNESDAY AM, JUNE 27<sup>TH</sup>, 2001

*Session Organizers:* Frank Register, The University of Texas at Austin; Supriyo Bandyopadhyay, University of Nebraska

**10:00 AM, VI.A.-1**

**Spin-Orbit Interaction of  $2^\circ$  in InAlAs/InAs Hetero-structures:** *Kanji Yoh<sup>1</sup>*; Toshihiro Doi<sup>1</sup>; Shin-ichiro Abe<sup>2</sup>; Yoshito Katano<sup>1</sup>; Hiroshi Ohno<sup>2</sup>; Kazuhisa Sueoka<sup>2</sup>; Koichi Mukasa<sup>2</sup>; <sup>1</sup>Hokkaido University, RCIQE, N13, W8, Kita-ku, Sapporo, Hokkaido 060-8628 Japan; <sup>2</sup>Hokkaido University, Grad. Sch. of Eng., N13, W8, Kita-ku, Sapporo, Hokkaido 060-8628 Japan

**10:20 AM (Student), VI.A.-2**

**Thermal Conductivity in Semiconductor Thin Films and Nanowires:** *Jie Zou<sup>1</sup>*; Alexander A. Balandin<sup>1</sup>; <sup>1</sup>University of California at Riverside, Dept. of Electl. Eng., Riverside, CA 92521 USA

**10:40 AM (Student), VI.A.-3**

**Quantum Mechanical Calculation of QCA Molecule Properties:** *Christopher J. Russo<sup>1</sup>*; *Craig S. Lent<sup>1</sup>*; <sup>1</sup>University of Notre Dame, Electl. Eng., 275 Fitzpatrick, Notre Dame, IN 46556 USA

**11:00 AM, VI.A.-4**

**Nano-Transistor Modeling: Two Dimensional Green's Function Method:** *A. Svizhenko<sup>1</sup>*; M. P. Anantram<sup>1</sup>; T. R. Govindan<sup>1</sup>; B. Biegel<sup>1</sup> <sup>1</sup>NASA, Ames Rsrch. Ctr., MS T27A-1, Moffett Field, CA 94035-1000 USA

**11:20 AM, VI.A.-5**

**A Coupled Schrödinger/Monte Carlo Technique for Quantum-Corrected Device Simulation:** *Brian Winstead<sup>1</sup>*; Umberto Ravaioli<sup>1</sup> <sup>1</sup>University of Illinois at Urbana-Champaign, Beckman Inst., Urbana, IL 61801 USA

**11:40 AM, VI.A.-6**

**Quantitative Prediction of Threshold Voltage Fluctuations in Sub-100 nm MOSFETs by a New Dopant Model:** *Hiroyuki Yamamoto<sup>1</sup>*; Yos-himitsu Okada<sup>1</sup>; Nobuyuki Sano<sup>1</sup>; <sup>1</sup>University of Tsukuba, Inst. of Appl. Phys., 1-1-1 Tennoudai, Tsukuba, Ibaraki, 305-8573 Japan

## Displays

WEDNESDAY AM, JUNE 27<sup>TH</sup>, 2001

*Session Organizer:* Tayo Akinwande, MIT

**10:10 AM, VI.B.-1 Invited**

**High Gamma Coatings for Plasma Display Panels: A Comparison:** *P. K. Bachmann*<sup>1</sup>; V. Van Elsbergen<sup>1</sup>; C. McGrath<sup>1</sup>; <sup>1</sup>Phillips Research Laboratories, Weissshausstrasse 2, D-52066 Aachen, Germany

**10:40 AM, VI.B.-2**

**Rare-Earth Doped GaN Electroluminescent Devices for Robust Flat Panel Displays:** *J. Heikenfeld*<sup>1</sup>; A.J. Steckl<sup>1</sup>; <sup>1</sup>University of Cincinnati, Nanoelectronics Lab, Cincinnati, OH 45221-0030 USA

**11:00 AM, VI.B.-3**

**Novel Three-Color Polymer Light-Emitting Devices for Passive-Matrix Flat Panel Displays:** *Ke Long*<sup>1</sup>; Min-Hao Lu<sup>1</sup>; Florian Pschenitzka<sup>1</sup>; J. C. Sturm<sup>1</sup>; <sup>1</sup>Princeton University, Department of Electrical Engineering, Center for Photonics and Optoelectronic Materials (POEM), Princeton, NJ 08544 USA

**11:20 AM, VI.B.-4**

**Flexible Liquid Crystal Displays Driven by Organic Thin Film Transistors on Polymeric Substrates:** *C. D. Sheraw*<sup>1</sup>; L. Zhou<sup>1</sup>; J. R. Huang<sup>1</sup>; L. Jia<sup>1</sup>; J. A. Nichols<sup>1</sup>; C. C. Kuo<sup>1</sup>; D. J. Gundlach<sup>1</sup>; T. N. Jackson<sup>1</sup>; M. G. Kane<sup>2</sup>; I. G. Hill<sup>2</sup>; M. S. Hammond<sup>2</sup>; J. Campi<sup>2</sup>; B. K. Greening<sup>2</sup>; J. Franc<sup>3</sup>; J. West<sup>3</sup>; <sup>1</sup>The Pennsylvania State University, Center for Thin Film Devices, University Park, PA 16802 USA; <sup>2</sup>Sarnoff Corporation, Solid State Display Laboratory, Princeton, NJ 08543 USA; <sup>3</sup>Kent State University, Liquid Crystal Institute, Kent, OH 44242 USA



## TFTs

**WEDNESDAY PM, JUNE 27<sup>TH</sup>, 2001**

*Session Organizer:* Hagen Klauk, Infineon Technologies

**2:00 PM, VII.A.-1 Invited**

**Organic-Inorganic Electronic Devices Based on Hybrid Perovskites:** *D. B. Mitzi*<sup>1</sup>; C. D. Dimitrakopoulos<sup>1</sup>; L. L. Kosbar<sup>1</sup>; <sup>1</sup>IBM T. J. Watson Research Center, Yorktown Heights, NY 10598 USA

**2:30 PM, VII.A.-2**

**CMOS Polysilicon Circuits on Flexible Steel Substrates:** *Ming Wu*<sup>1</sup>; Sigurd Wagner<sup>1</sup>; <sup>1</sup>Princeton University, Department of Electrical Engineering, Princeton, NJ 08544 USA

**2:50 PM, VII.A.-3**

**High-Performance Thin-Film Transistor Fabricated on Poly-Si Films Prepared by Metal Imprint Technology:** *Kenji Makihira*<sup>1</sup>; Masahito Yoshii<sup>1</sup>; Tanemasa Asano<sup>1</sup>; <sup>1</sup>Kyushu Institute of Technology, Center for Microelectronic Systems, 680-4 Kawazu, Iizuka, Fukuoka 820-8502, Japan

**3:10 PM, VII.A.-4**

**Excimer Laser Annealed, Poly-Si Thin Film Transistors for Flat Panel Imager Application:** *J. P. Lu*<sup>1</sup>; K. Van Schuylenbergh<sup>1</sup>; J. Ho<sup>1</sup>; Y. Wang<sup>1</sup>; P. Nysten<sup>1</sup>; J. B. Boyce<sup>1</sup>; R. A. Street<sup>1</sup>; <sup>1</sup>Xerox Palo Alto Research Center, 3333 Coyote Hill Road, Palo Alto, CA 94304 USA

**3:30 PM Break**

**3:50 PM, VII.A.-5**

**Amorphous Si TFTs on Plastically-Deformed Substrates with 3-D Shapes:** *P. I. Hsu*<sup>1</sup>; H. Gleskova<sup>1</sup>; Z. Suo<sup>1</sup>; S. Wagner<sup>1</sup>; J. C. Sturm<sup>1</sup>; <sup>1</sup>Princeton University, Center for Photonics and Optoelectronic Materials (POEM), Princeton, NJ 08544 USA

**4:10 PM, VII.A.-6**

**Gate Control in Ultra-Short Channel Double-Gate MOSFETs Accounting for 2D and Quantum Confinement Effects:** *M. Mouis*<sup>2</sup>; F.-N. Genin<sup>1</sup>; A. Poncet<sup>1</sup>; <sup>1</sup>Laboratoire de Physique de la Matière, UMR-CNRS n° 5511, INSA-Lyon 20, Avenue Albert Einstein, F-69621 Villeurbanne, France; <sup>2</sup>CEA-Grenoble, LETI/DTS/CPMA, 17 rue des Martyrs, 38054 Grenoble Cedex 9 France

# Wide Bandgap Semiconductors

WEDNESDAY PM, JUNE 27<sup>TH</sup>, 2001

*Session Organizer:* Anant Agarwal, CREE

**2:00 PM, VII.B.-1 Invited**

**K-Band GaN Power HFET's with 6.6 W/mm CW Saturated Output Power Density and 35% Power Added Efficiency at 20 GHz:** *Miro Micovic<sup>1</sup>; Jeong S. Moon<sup>1</sup>; Ara Kurdoghlian<sup>1</sup>; Paul Hashimoto<sup>1</sup>; Danny Wong<sup>1</sup>; Loren McCray<sup>1</sup>; Tahir Hussain<sup>1</sup>; Paul Janke<sup>1</sup>*; <sup>1</sup>HRL Laboratories LLC, 3011 Malibu Canyon Road, Malibu, CA 90265 USA

**2:30 PM, VII.B.-2**

**Linearity of High Al-Content AlGaIn/GaN HEMTs:** *T. Jenkins<sup>1</sup>; L. Kehias<sup>1</sup>; P. Parikh<sup>2</sup>; Y.-F. Wu<sup>2</sup>; P. Chavarkar<sup>2</sup>; M. Moore<sup>2</sup>; U. Mishra<sup>2</sup>*; <sup>1</sup>Air Force Research laboratory, 2241 Avionics Circle, Wright-Patterson AFB, OH 45433 USA; <sup>2</sup>Cree Lighting Company, 340 Storke Road, Goleta, CA 93117 USA

**2:50 PM, VII.B.-3**

**Demonstration of Push-Pull Operation of AlGaIn/GaN HEMTs on SiC:** *Jong-Wook Lee<sup>1</sup>; Sungjae Lee<sup>1</sup>; Keven J. Webb<sup>1</sup>*; <sup>1</sup>Purdue University, School of Electrical and Computer Engineering, West Lafayette, IN 47907 USA

**3:10 PM, VII.B.-4**

**On Development of 600-850 V 6H-SiC LDMOS Transistors Using Silane-Ambient Implant Anneal:** *I. Sankin<sup>1</sup>; J. B. Casady<sup>1</sup>; J. B. Dufrene<sup>1</sup>; W. A. Draper<sup>1</sup>; J. Kretchmer<sup>2</sup>; J. Vandersand<sup>1</sup>; V. Kumar<sup>1</sup>; M. S. Mazzola<sup>1</sup>; S. E. Sadow<sup>1</sup>*; <sup>1</sup>Mississippi State University, Electrical & Computer Engineering Department, Box 9571, Mississippi State, MS 39762-9571 USA; <sup>2</sup>General Electric Corporate Research & Development Center, Schenectady, NY USA

**3:30 Break**

**3:50 PM, VII.B.-5**

**An X-Band Silicon Carbide IMPATT Diode:** *Luo Yuan<sup>1</sup>; Michael R. Melloch<sup>1</sup>; James A. Cooper, Jr.<sup>1</sup>; Kevin J. Webb<sup>1</sup>*; <sup>1</sup>Purdue University, School of Electrical and Computer Engineering, West Lafayette, IN 47907 USA

**4:10 PM, VII.B.-6**

**The Effect of Emitter Implant and Anneal on High-Voltage 4H-SiC BJTs:** *Yi Tang<sup>1</sup>; Jeffrey B. Fedison<sup>1</sup>; T. Paul Chow<sup>1</sup>*; <sup>1</sup>Rensselaer Polytechnic Institute, Center for Integrated Electronics and Electronic Manufacturing, Troy, NY 12180 USA

**4:30 PM, VII.B.-7**

**Diamond Surface Channel FET with  $f_{\max}$  Above 30 GHz:** *A. Aleksov<sup>1</sup>; A. Denisenko<sup>1</sup>; U. Spitzberg<sup>1</sup>; E. Köhn<sup>1</sup>*; <sup>1</sup>University of Ulm, Dept. of Electron Devices and Circuits, Albert-Einstein-Allee 45, D-89081 Ulm, Germany

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